

WHAT IS CLAIMED IS:

- 1 1. A method of manufacturing an integrated circuit, the method
2 comprising:
3 providing a gate dielectric layer above a top surface of a
4 substrate;
5 providing a silicon and nitrogen containing layer above the
6 gate dielectric layer;
7 providing an oxide layer above the silicon and nitrogen
8 containing layer;
9 selectively etching the oxide layer to form a first trench in
10 the oxide layer;
11 selectively etching the silicon and nitrogen containing layer
12 to form a second trench in the silicon and nitrogen containing layer, the
13 second trench being narrower than the first trench and being disposed
14 below the first trench; and
15 providing a gate conductor material in the first trench and
16 the second trench.
- 1 2. The method of claim 1, further comprising removing the
2 oxide layer.
- 1 3. The method of claim 2, further comprising:
2 removing portions of the silicon and nitrogen containing
3 layer, whereby a pair of spacers remain underneath the gate conductor
4 material in the first trench.
- 1 4. The method of claim 3, wherein the gate conductor material
2 is removed by a polishing process.

1 5. The method of claim 3, wherein the silicon and nitrogen
2 containing layer includes silicon rich nitride.

1 6. The method of claim 1, wherein the selective etching the
2 silicon and nitrogen containing layer includes a RELACS process.

1 7. The method of claim 1, wherein the silicon and nitrogen
2 containing layer includes SiON or silicon rich nitride.

1 8. The method of claim 7, wherein the silicon and nitrogen
2 containing layer is a silicon rich nitride layer.

1 9. The method of claim 1, wherein a width of the first trench is
2 at least 250 Å and less than 1600 Å.

1 10. The method of claim 9, wherein the width of the second
2 trench is at least 400 Å and less than 2100 Å.

1 11. A method of manufacturing an ultra-large scale integrated
2 circuit including a transistor with a T-shaped gate conductor, the method
3 includes steps of:

4 providing a first layer above a substrate, the first layer being
5 a silicon rich nitride layer or a silicon oxynitride layer;

6 providing an oxide layer over the first layer;

7 forming a first trench in the oxide layer;

8 forming a second trench in the first layer, the second trench
9 having a smaller width than the first trench; and

10 providing a gate conductor material in the first trench and in
11 the second trench to form the T-shaped gate conductor.

1 12. The method of claim 11, further comprising removing the
2 oxide layer.

1 13. The method of claim 12, further comprising removing
2 portions of the first layer to leave spacers underneath the gate conductor
3 material in the first trench, the removal process utilizing the gate
4 conductor material as a mask.

1 14. The method of claim 13, wherein the first layer is silicon rich
2 nitride.

1 15. A method of manufacturing a gate conductor for an
2 integrated circuit, the method comprising:

3 providing a first layer above a gate dielectric layer, the gate
4 dielectric layer being above a substrate, the first layer including silicon
5 oxynitride or silicon rich nitride;

6 forming an aperture in the first layer utilizing a RELACS
7 process;

8 filling the aperture with a gate conductor material; and
9 removing the gate conductor material above the first layer.

1 16. The method of claim 15, further comprising:

2 providing an oxide layer above the first layer and forming an
3 aperture in the oxide layer before forming the aperture in the first layer.

1 17. The method of claim 16, wherein the gate conductor material
2 is doped or undoped polysilicon material.

1 18. The method of claim 17, wherein a T-shaped gate conductor
2 is formed.

1 19. The method of claim 16, wherein the gate conductor material
2 is also provided in the aperture in the oxide layer.

- 1 20. The method of claim 16, wherein the oxide layer is silicon
2 dioxide.

Variable	Mean	SD	Min	Max
Age	35.2	12.5	18	65
Gender	1.2	0.4	1	2
Marital status	1.5	0.5	1	3
Education	12.8	2.1	9	16
Income	1.8	0.6	1	3
Occupation	1.5	0.5	1	3
Religion	1.2	0.4	1	2
Health status	1.5	0.5	1	3
Life satisfaction	1.8	0.6	1	3
Stress level	1.5	0.5	1	3
Depression	1.2	0.4	1	2
Loneliness	1.5	0.5	1	3
Self-esteem	1.8	0.6	1	3
Resilience	1.5	0.5	1	3
Optimism	1.8	0.6	1	3
Gratitude	1.5	0.5	1	3
Forgiveness	1.2	0.4	1	2
Empathy	1.5	0.5	1	3
Compassion	1.8	0.6	1	3
Kindness	1.5	0.5	1	3
Generosity	1.2	0.4	1	2
Patience	1.5	0.5	1	3
Humility	1.8	0.6	1	3
Modesty	1.5	0.5	1	3
Shyness	1.2	0.4	1	2
Introversion	1.5	0.5	1	3
Extroversion	1.8	0.6	1	3
Sensitivity	1.5	0.5	1	3
Emotionality	1.2	0.4	1	2
Stability	1.5	0.5	1	3
Control	1.8	0.6	1	3
Order	1.5	0.5	1	3
Neatness	1.2	0.4	1	2
Organization	1.5	0.5	1	3
Planning	1.8	0.6	1	3
Decision making	1.5	0.5	1	3
Problem solving	1.2	0.4	1	2
Adaptability	1.5	0.5	1	3
Flexibility	1.8	0.6	1	3
Openness	1.5	0.5	1	3
Curiosity	1.2	0.4	1	2
Imagination	1.5	0.5	1	3
Creativity	1.8	0.6	1	3
Innovation	1.5	0.5	1	3
Risk taking	1.2	0.4	1	2
Change	1.5	0.5	1	3
Progress	1.8	0.6	1	3
Growth	1.5	0.5	1	3
Development	1.2	0.4	1	2
Learning	1.5	0.5	1	3
Knowledge	1.8	0.6	1	3
Wisdom	1.5	0.5	1	3
Understanding	1.2	0.4	1	2
Insight	1.5	0.5	1	3
Intuition	1.8	0.6	1	3
Spirituality	1.5	0.5	1	3
Religiosity	1.2	0.4	1	2
Devotion	1.5	0.5	1	3
Worship	1.8	0.6	1	3
Prayer	1.5	0.5	1	3
Meditation	1.2	0.4	1	2
Yoga	1.5	0.5	1	3
Exercise	1.8	0.6	1	3
Health	1.5	0.5	1	3
Well-being	1.2	0.4	1	2
Quality of life	1.5	0.5	1	3
Satisfaction	1.8	0.6	1	3
Life	1.5	0.5	1	3
Existence	1.2	0.4	1	2
Being	1.5	0.5	1	3
Consciousness	1.8	0.6	1	3
Awareness	1.5	0.5	1	3
Perception	1.2	0.4	1	2
Experience	1.5	0.5	1	3
Knowledge	1.8	0.6	1	3
Understanding	1.5	0.5	1	3
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